

Serial No. 09/928,474



Docket No.: 006301 USA/Consilium/Consilium

PATENT/OFFICIAL

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of :
Badri N. KRISHNAMURTHY et al. :
Serial No. 09/928,474 : Group Art Unit: 2812
Filed: August 14, 2001 : Examiner: Andre' C. Stevenson
For: EXPERIMENT MANAGEMENT SYSTEM, METHOD AND MEDIUM

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This submission does not constitute a representation that a search has been made or that no better art exists and does not constitute an admission or representation that any of the listed documents is material or constitutes prior art. If it should be determined that any of the listed documents does not constitute prior art under the United States law, Applicants reserve the right to present to the Office the relevant facts and law regarding the appropriate status of such

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document.

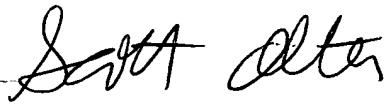
The references listed on Sheet 1 of the attached PTO-1449 Forms were cited in a patentability investigation and/or a corresponding foreign or PCT application relating to the above-referenced application. The remaining references are from potentially related patent applications, and possibly other sources.

The referenced patent application was finally rejected on June 3, 2004. Applicants petition for consideration of the enclosed documents by the Examiner. The petition fee of \$180.00 pursuant to 37 CFR § 1.17(p) is attached. The Commissioner is authorized to charge any deficiency in any fees pursuant to 37 CFR § 1.17 associated with this communication and to credit any excess payment to Deposit Account No. 08-0219.

Respectfully submitted,

Wilmer Cutler Pickering Hale and Dorr LLP

The PTO did not receive the following
listed items(s) Fee \$180.00


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SHEET 2 OF 7

INFORMATION DISCLOSURE
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